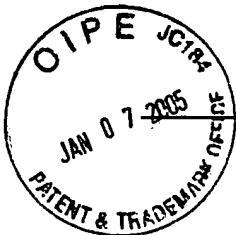


IFW



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE
(Case No. 213.007-US)

In the Application of: **YE ET AL.**

Serial No: **10/815,573**

Filed: **APRIL 1, 2004**

Title: **SYSTEM AND METHOD OF LITHOGRAPHY
SIMULATION**

) Group Art Unit: **1756**

) Before Examiner:

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

I hereby certify that this correspondence is being deposited with the United States Postal Service as first class mail with sufficient postage in an envelope addressed to the Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450 on January 3, 2005
Date

Michiko Siter
(person signing this certificate)

Michiko Siter
Signature

SECOND INFORMATION DISCLOSURE STATEMENT

Dear Sir:

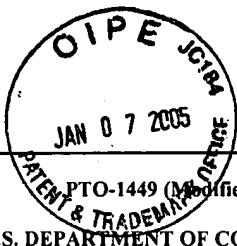
Submitted herewith is one (1) sheet of a modified Form PTO-1449. A copy of each document cited on the attached Form PTO-1449 is also submitted.

It is respectfully requested that the Examiner make his/her consideration of these references formally of record with the initial Office Action.

Respectfully submitted,

Date: January 3, 2005

Neil A. Steinberg, Reg. No. 34,735
Telephone No. 650-968-8079



Sheet 1 of 1

PTO-1449 (Modified) U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE INFORMATION DISCLOSURE STATEMENT BY APPLICANT	ATTY. DOCKET NO. 213.007-US	SERIAL NUMBER 10/815,573
	APPLICANT(S) Ye et al.	
	FILING DATE April 1, 2004	GROUP ART UNIT 1756

U.S. PATENT DOCUMENTS

EXAMINER INITIALS	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE

FOREIGN PATENT DOCUMENTS

EXAMINER INITIALS	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUB CLASS	TRANSLATION YES/NO	

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

	"Compact Formulation of Mask Error Factor for Critical Dimension Control in Optical Lithography", Zhang, et al., Microlithography, SPIE 2002, 4 pages
	"A Simulation Framework for Lithography Process Monitoring and Control Using Scatterometry", Bao et al., AEC/APC 2001, 4 pages
	"A Novel Approach for Modeling and Diagnostics of Lithography Process", Wang et al., AEC/APC 2001, 5 pages
	"Optimum sampling for characterization of systematic variation in photolithography", Cain et al., Microlithography, SPIE 2002, 13 pages
	"Electrical linewidth metrology for systematic CD variation characterization and causal analysis", Cain et al., Microlithography, SPIE 2003, 12 pages

EXAMINER	DATE CONSIDERED
EXAMINER: Initial citation if reference was considered. Draw line through citation if not in conformance to MPEP 609 and not considered. Include copy of this form with next communication to applicant.	